

Title (en)
DEVICE FOR MONITORING AND CALIBRATING OXIDE CHARGE MEASUREMENT EQUIPMENT AND METHOD THEREFOR

Title (de)
APPARAT ZUR KONTROLLE UND KALIBRIERUNG VON OXIDLADUNGSMESSGERÄTEN UND ZUGEHÖRIGE METHODE

Title (fr)
DISPOSITIF DESTINE A CONTROLER ET A CALIBRER UN EQUIPEMENT DE MESURE DE CHARGE D'OXYDE ET PROCEDE CORRESPONDANT

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Application
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Priority
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Abstract (en)
[origin: WO0170438A1] A stabilized wafer for monitoring and calibrating oxide charge test equipment. The stabilized wafer comprises; a silicon wafer, a SiO₂ layer of at least 100 angstroms upon the silicon wafer, and a phosphosilicate glass layer containing phosphorus formed in the SiO₂ layer for providing the stabilized wafer by stabilizing an SiO₂ interface and containing oxygen ions. The stabilized wafer is used for monitoring and calibrating oxide charge test equipment.

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